

Workshop/IRTG Oslo Sep 2009 - "Detector Technology"

	Group I	Group II
Monday 28 Sep Morning <i>Lunch 14-15</i>	<u>Opening, Safety issues: 10 -11</u> Lab cleanroom 11 – 14 (VB, RS) Cleaning of wafers, Field oxidation, Lithography 1, (opening of Source & Drain), Etching, Loading of wafers for implantation	<u>Opening, Safety issues: 10 - 11</u> Lectures 11 – 13 (BGS) Semiconductor materials and basic semiconductor physics, pn-junction
Monday 28 Sep Afternoon	Lectures 15 – 18 (BGS) Semiconductor materials and basic semiconductor physics, pn-junction	Lab cleanroom 15 – 19 (VB, RS) Safety issues, cleaning of wafers, Field oxidation, Lithography 1, (opening of Source & Drain), Etching, Loading of wafers for implantation
Tuesday 29 Sep Morning <i>Lunch 12-13</i>	Lab cleanroom 8 – 12 (VB, RS) Lithography 2 (remove field oxide from gate), Etching, Gate oxidation	Lectures 9 – 12 (BGS) Si device processing technology, MOSFET, Si detectors and radiation hardness
Tuesday 29 Sep Afternoon	Lectures 13 – 16 (BGS) Si device processing technology, MOSFET, Si detectors and radiation hardness	Lab cleanroom 13 – 17 (VB, RS) Lithography 2 (remove field oxide from gate), Etching, Gate oxidation
Wednesday 30 Sep Morning <i>Lunch 12-13</i>	Lab cleanroom 8 – 12 (VB, RS) Lithography 3 (removal of gate oxide from S&D), Etching, Loading wafers for contact deposition	Lectures 9 – 11:30 (DTW) MEMS + visit SINTEF area
Wednesday 30 Sep Afternoon <i>Evening: dinner</i>	Lectures 15 – 17:30 (DTW) MEMS + visit SINTEF area	Lab cleanroom 13 – 17 (VB, RS) Lithography 3 (removal of gate oxide from S&D), Etching, Loading wafers for contact deposition
Thursday 1 Oct Morning <i>Lunch 12-13</i>	Lab cleanroom 8 – 12 (VB, RS) Lithography 4 (define contacts for G,S,D), Etching, Contact annealing	Lectures 9 – 11 (AK) 3-D Si detectors
Thursday 1 Oct Afternoon	Lectures 13 – 15 (AK) 3-D Si detectors	Lab cleanroom 13 – 17 (VB, RS) Lithography 4 (define contacts for G,S,D), Etching, Contact annealing

<p>Friday 2 Oct Morning</p> <p><i>Lunch 12-13</i></p>	<p>Lab cleanroom 9 – 12 (VB, RS) Evaluation and electrical characterization of fabricated MOSFET's, delivery of lab report</p>	
<p>Friday 2 Oct Afternoon</p>		<p>Lab cleanroom 12 – 15 (VB, RS) Evaluation and electrical characterization of fabricated MOSFET's, delivery of lab report</p>

Venue: MiNaLab – Gaustadalleen 23 C, Oslo
Lab: Clean room UiO, Floor II
Lectures: Galleria, Floor II

VB = Viktor Bobal (UiO)

AK = Angela Kok (SINTEF)

RS = Ramon Schifano (UiO)

DTW = Dag T. Wang (SINTEF and UiO)

BGS = Bengt Svensson (UiO)

Lunch is served in the cafeteria of Forskningsparken, 4 mins walk from MiNaLab.